

0.1 -1 μm.

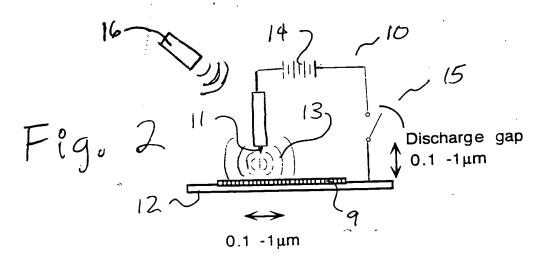
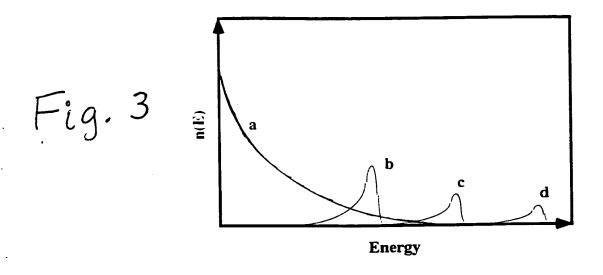
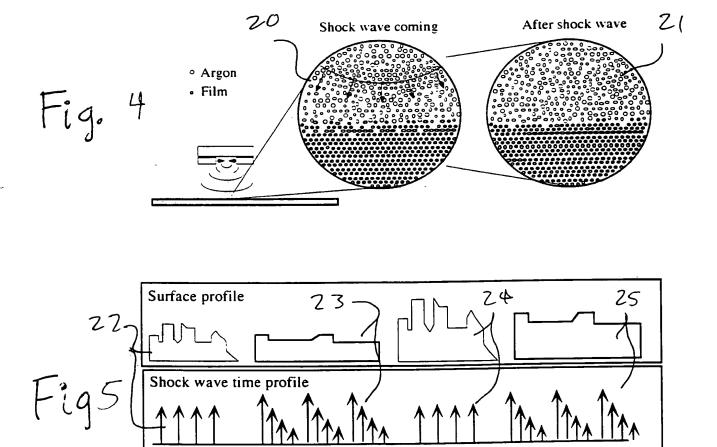
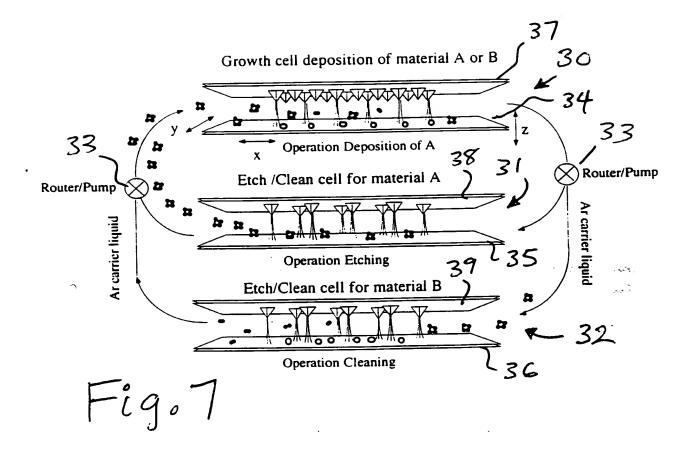


Fig. 6

Accepted National Critical Heat of Heat							
	Atomic	Melt.	Boiling	Critical	Critical	Heat of	
Liquid	Number	point	point	Temp.	Pressure	Vaporisat.	Capacity
		i°KI	°K	[°K]	Bar	[10 ³ JK ⁻¹ kg ⁻¹]	[JK ⁻¹ kg ⁻¹]
Н,	1	13.8	20.3	33.3	17	310	14200
N,	7	63.0	77,4	126.2	34	200	1040
0,	8	54.8	90.2	154.6	51	213	920
F,	9	55.5	85.4	144,0	57	316	750
Ne	10	24.5	27.0	54.0	27	86	1030
Ar	18	83.8	87.3	150.8	48	158	520
Cla	17	171.6	239.1	+17,0	77	282	500
Kr	36	116.6	120	209.4	55	108	
	<u> </u>				59	102	-
Xe Xe	36 54	161.3	165.1	289.7	59		-







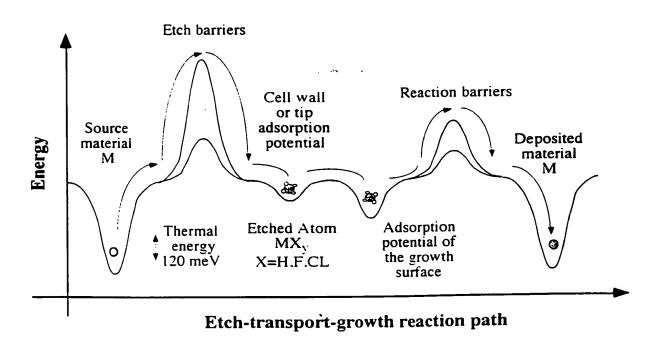
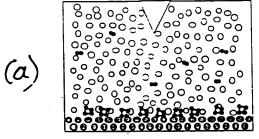
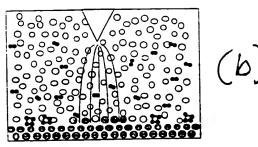


Fig. 10

Fig. 8



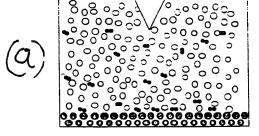
Before nanodischarge
Physisorption of etched resource atom



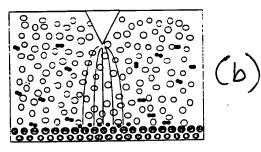
Weak nanodischarge for electron induced dissociative chemisorption of etched resource atom or deposition

Fig. 9

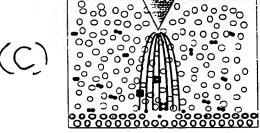
- o Argon o Resource atom 😄 Etched resource atom
- Etchant molecule



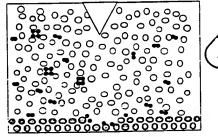
Before nanodischarge Physisorption of etchant molecules



Weak nanodischarge for electron induced dissociative chemisorption



Strong nanodischarge Electron induced chemical etching



After nanodischarge re-physisorption of etchant molecules

